

## Change of Microhardness of Amorphous Thin-Films of the System Ge-As-Se Under the Influence of Laser Irradiation

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This paper presents the results of studies of photoinduced changes in microhardness of amorphous films  $\text{Ge}_x\text{As}_y\text{Se}_{100-x-y}$  under influence of laser irradiated (laser power of 50 mW, wavelength of 655 nm). For realization of researchers chalcogenides glasses for such syllables were prepared:  $\text{Ge}_4\text{As}_4\text{Se}_{92}$ ,  $\text{Ge}_9\text{As}_9\text{Se}_{82}$ ,  $\text{Ge}_8\text{As}_{32}\text{Se}_{60}$ ,  $\text{Ge}_{16}\text{As}_{24}\text{Se}_{60}$ ,  $\text{Ge}_{24}\text{As}_{16}\text{Se}_{60}$ ,  $\text{Ge}_{32}\text{As}_8\text{Se}_{60}$  and  $\text{Ge}_{40}\text{Se}_{60}$ . The thin films were got thermal evaporation method of glasses by analogical syllables in a vacuum ( $10^{-3}$  Pa) on surface from quartz glass. Measuring of microhardness of  $H$  was conducted by means of PMT-3 instrument with the used of indenter of Vickers on-loading 0.05 Pa. At including of laser microhardness exponentially diminishes during the first 25-30 min in dependence on chemical composition lowering of microhardness of films makes a 10 - 27 %. Increase of time of irradiation over 30 min results in stabilizing of microhardness.

It is educed that at increase of mane coordinating number of  $Z$  in an interval a 2.12 - 2.48 size  $\Delta H$  changes poorly enough. At  $Z=2.67$  ( $\text{Ge}_{24}\text{As}_{16}\text{Se}_{60}$ ) there are the minimum relative photoinduced changes of microhardness. At the increase of  $Z$  from 2.67 to 2.80 sizes  $\Delta H$  swiftly grows approximately in 7 times ( $\text{Ge}_{40}\text{Se}_{60}$ ). The indicated intervals of the photoinduced changes of microhardness of films of  $\text{Ge}_x\text{As}_y\text{Se}_{100-x-y}$  correlate with position of areas of glasses with different structural flexibility on the diagram of glass formation in the system Ge - As - Se. As a point at  $Z=2.67$  is a 2d-3d topological structural transit point is possible to assert that the maximal photoinduced changes of mechanical parameters of chalcogenide glasses of the system Ge - As-Se, take place in glasses with a three-dimensional structure. This feature can be explained within the structure of intermolecular structural model of the photoinduced plasticity of chalcogenides glasses. The structure of films of the system Ge - As - Se at  $Z > 2.67$  under the action of laser irradiation passes the broken of the homopolar bonds in (As - As, Ge - Ge) and transformation of formed by them has volume (3-measurable) structural units of the plenary trivial oriented complexes. As a result of such processes structure of dimension and it structural has inflexibility fall down.

Reduction of the relative photoinduced changes of hardness is at  $Z < 2.67$  it can be contingently the subzero dimension of structure in the initial films of system  $\text{Ge}_x\text{As}_y\text{Se}_{100-x-y}$  by irradiation.